

FIGURE 1A

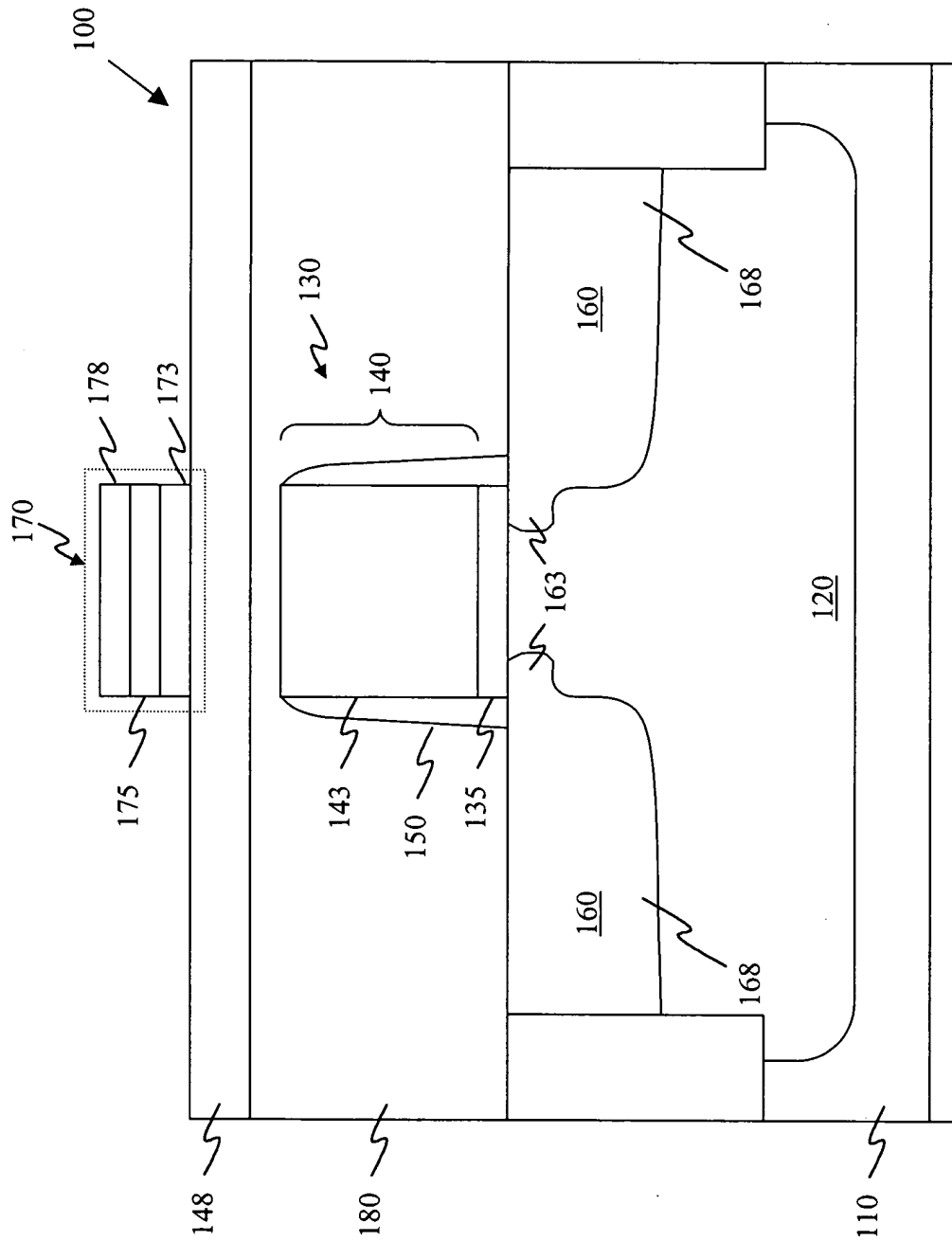


FIGURE 1B

200

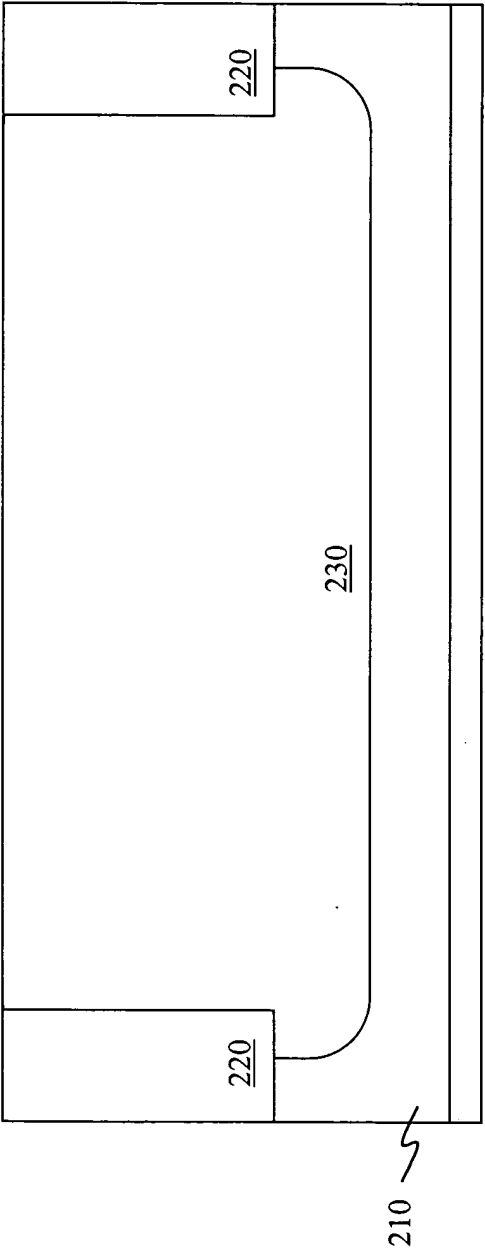


FIGURE 2

200

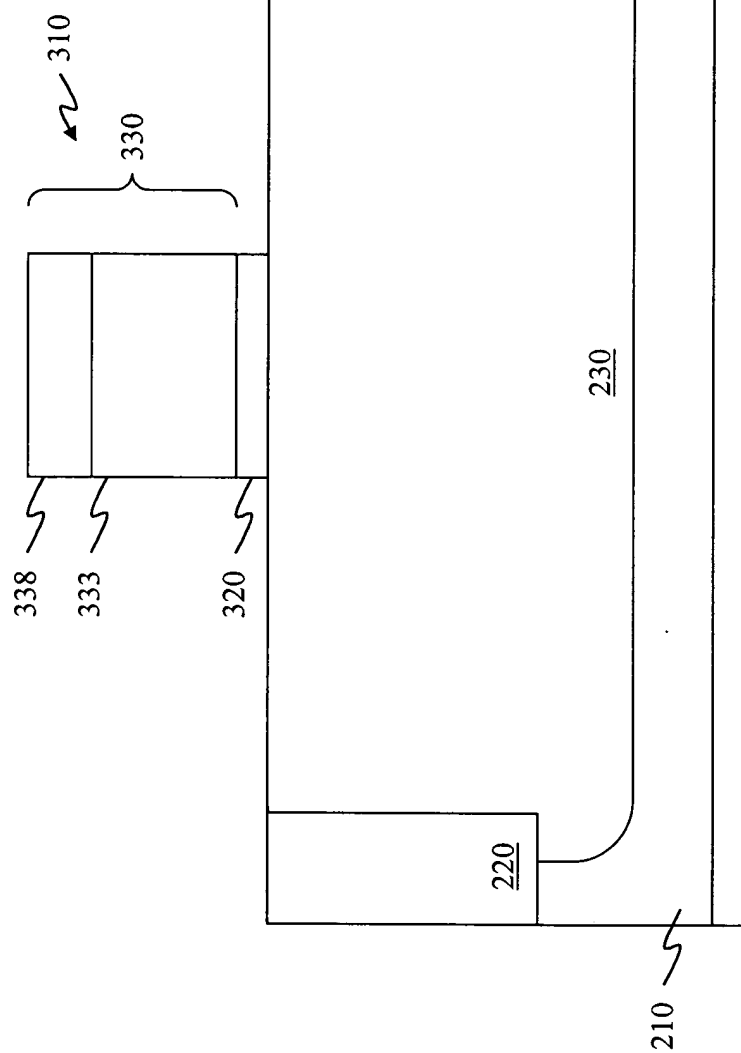


FIGURE 3

200

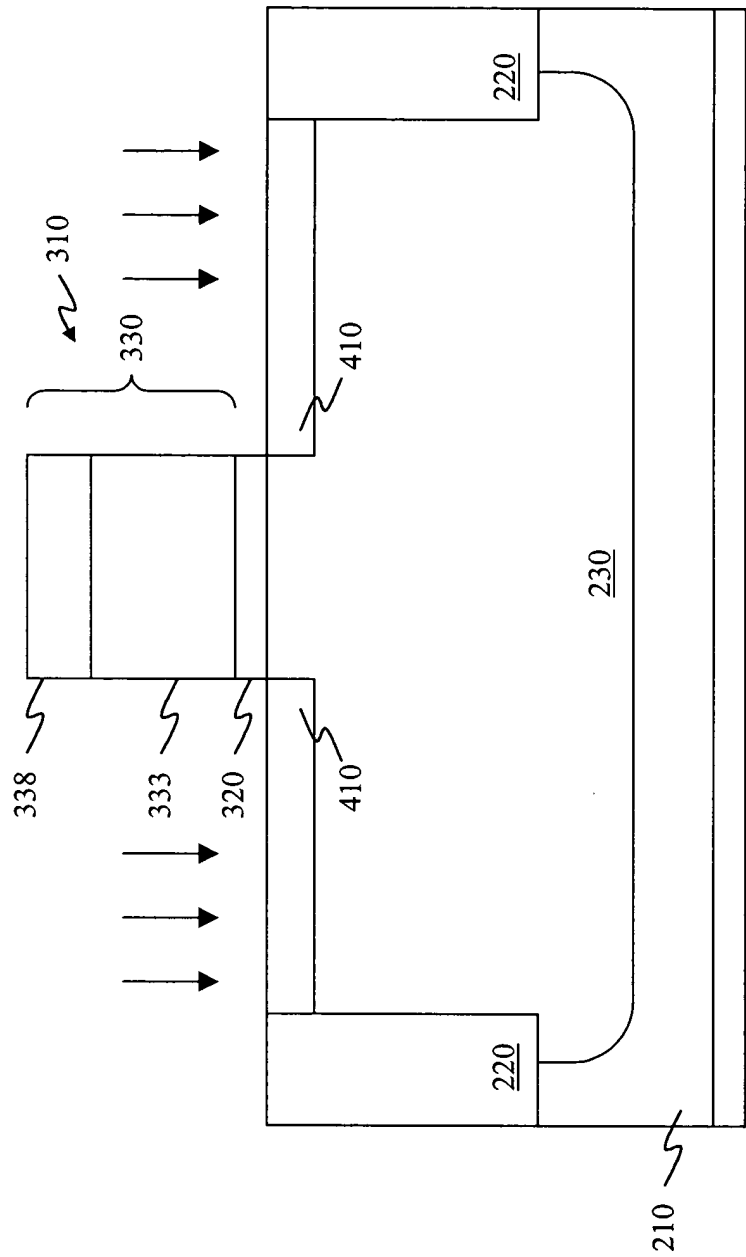


FIGURE 4

200

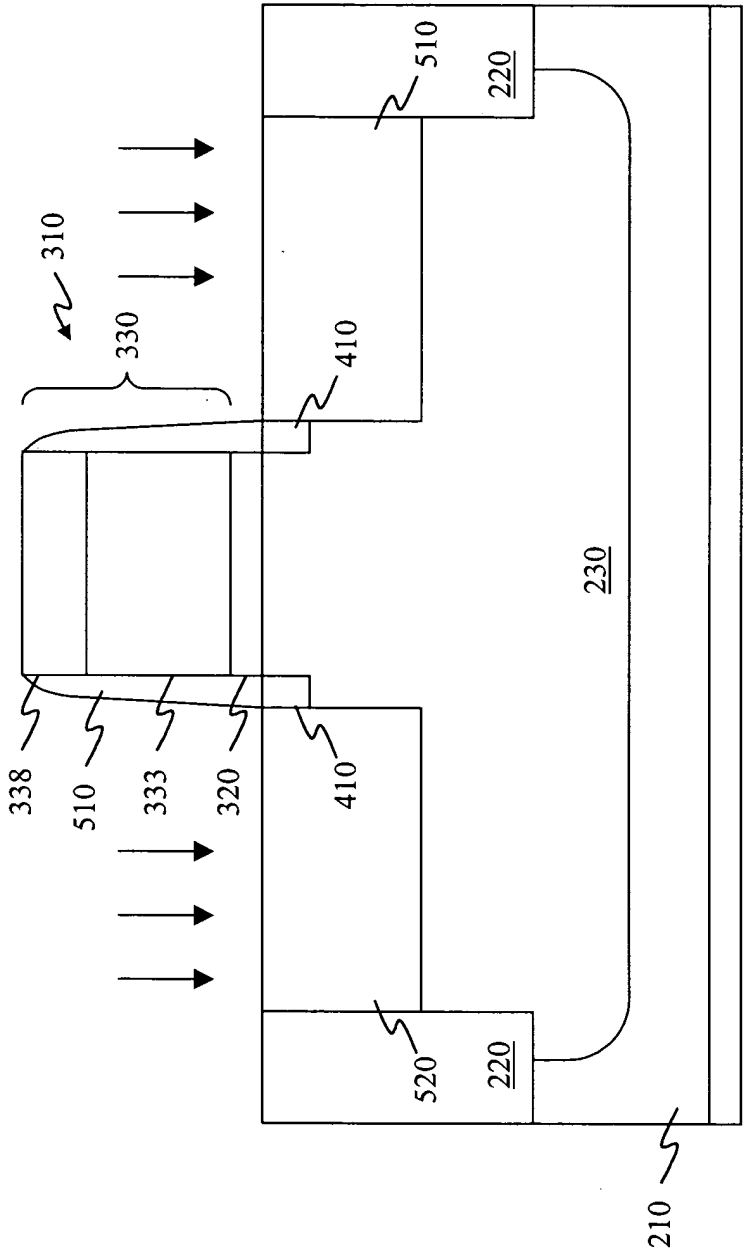


FIGURE 5

200

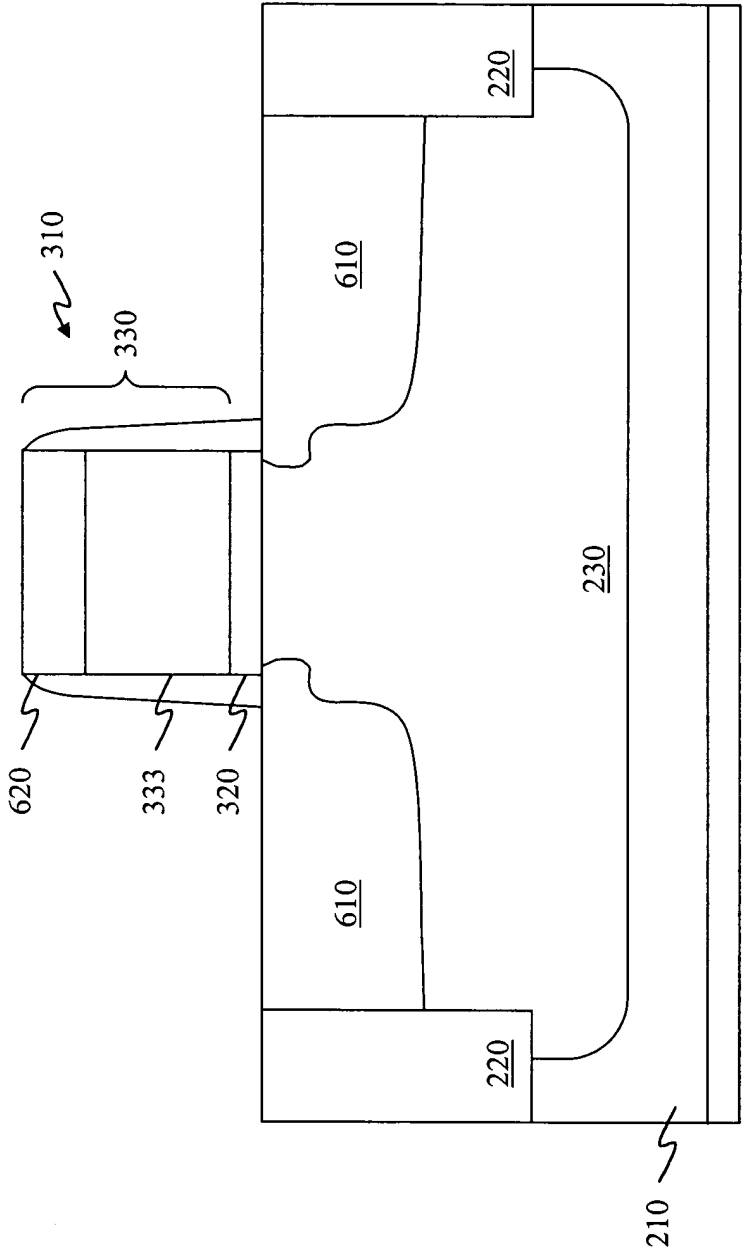


FIGURE 6

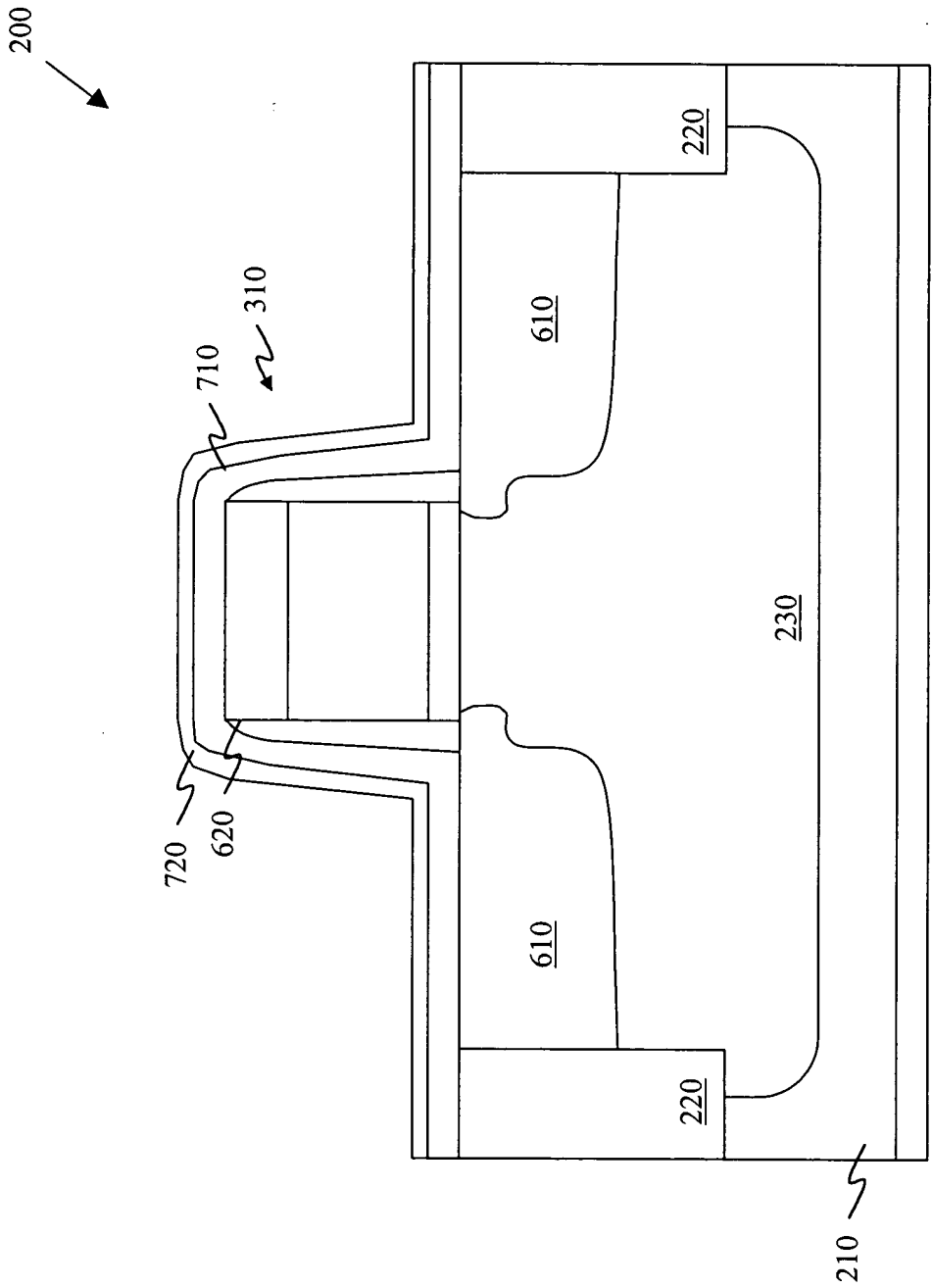


FIGURE 7

200

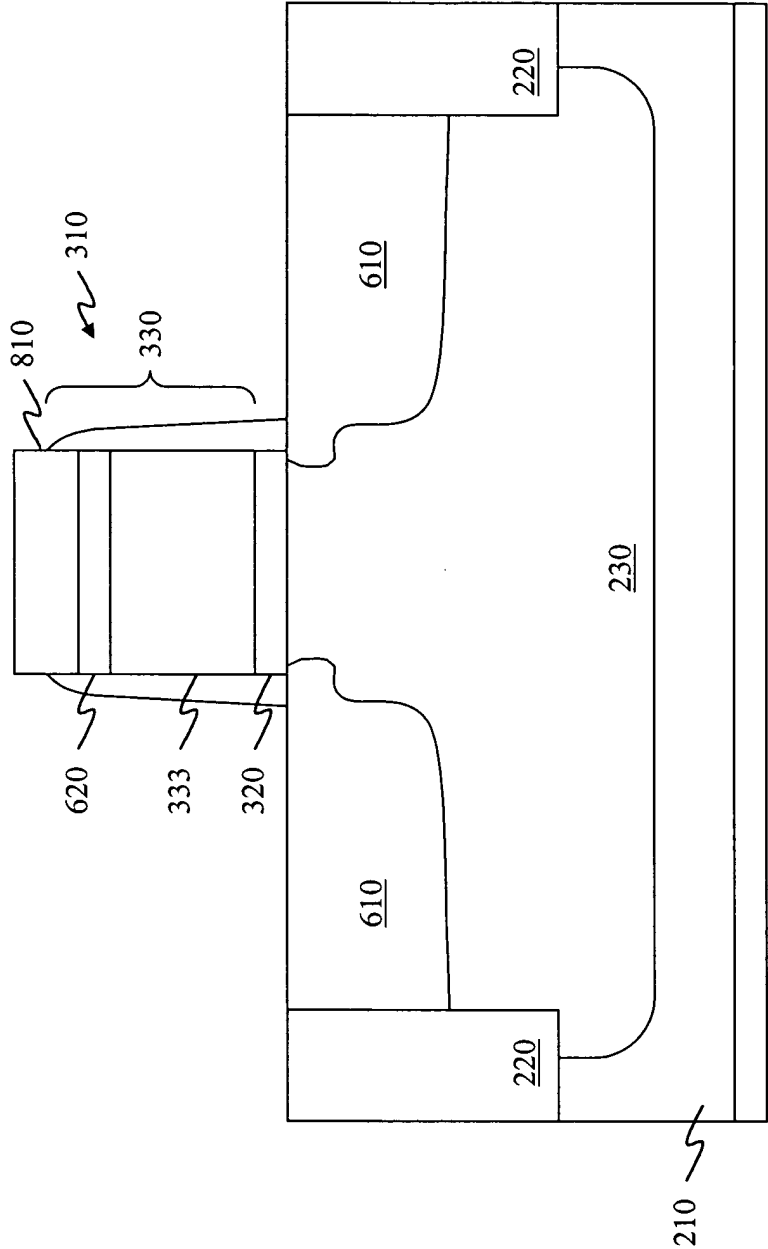


FIGURE 8

200

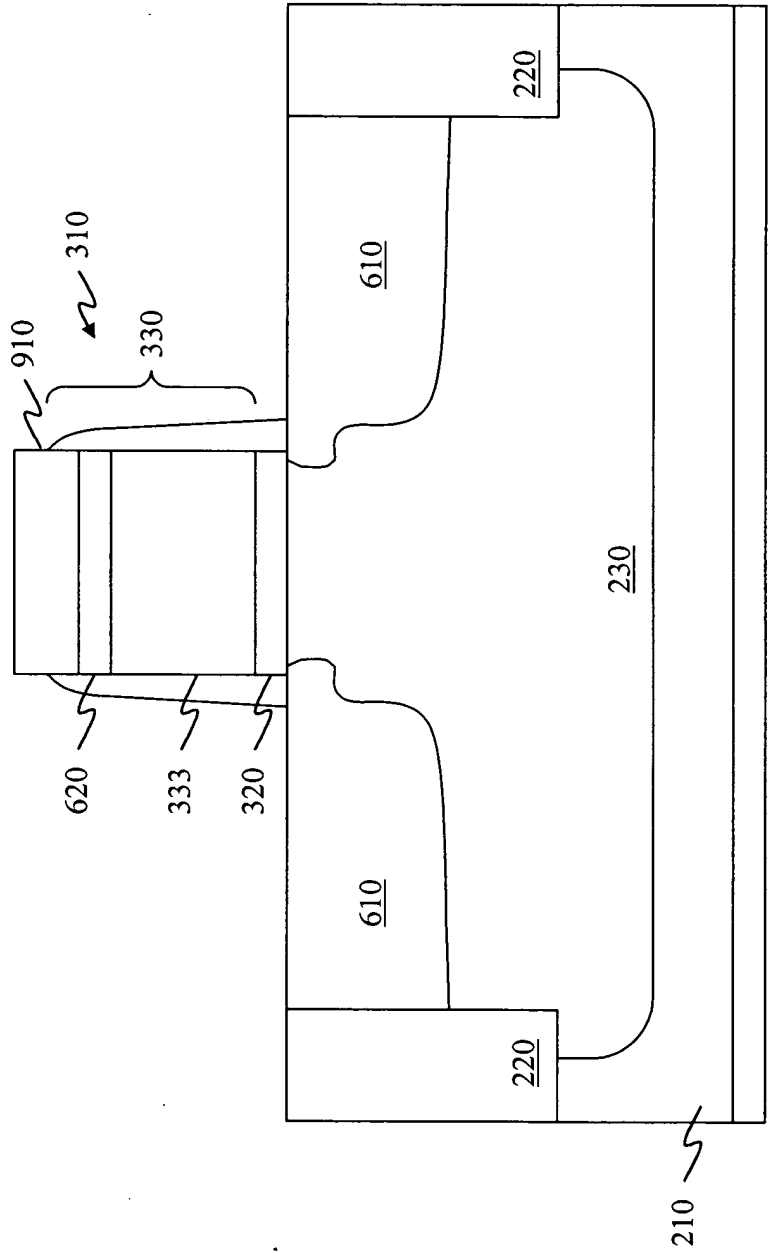


FIGURE 9

1000 ↗

TI-35669

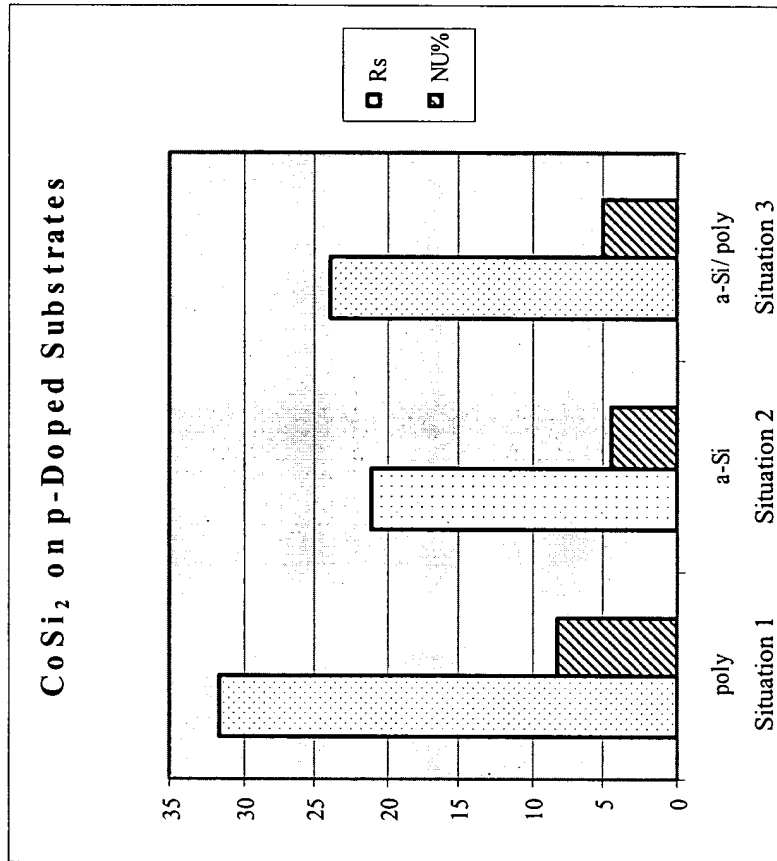


FIGURE 10

1100
↗

Surface Roughness by AFM

Situation	RMS[nm]	test1	test2	test3
1	3.000	3.116	2.976	2.909
2	1.621	1.558	1.659	1.645
3	2.064	1.904	2.387	1.901

- Situation 1 – CoSi₂ formed on poly-Si
- Situation 2 – CoSi₂ formed on a-Si
- Situation 3 – CoSi₂ formed on a-Si/poly stack

FIGURE 11

1200

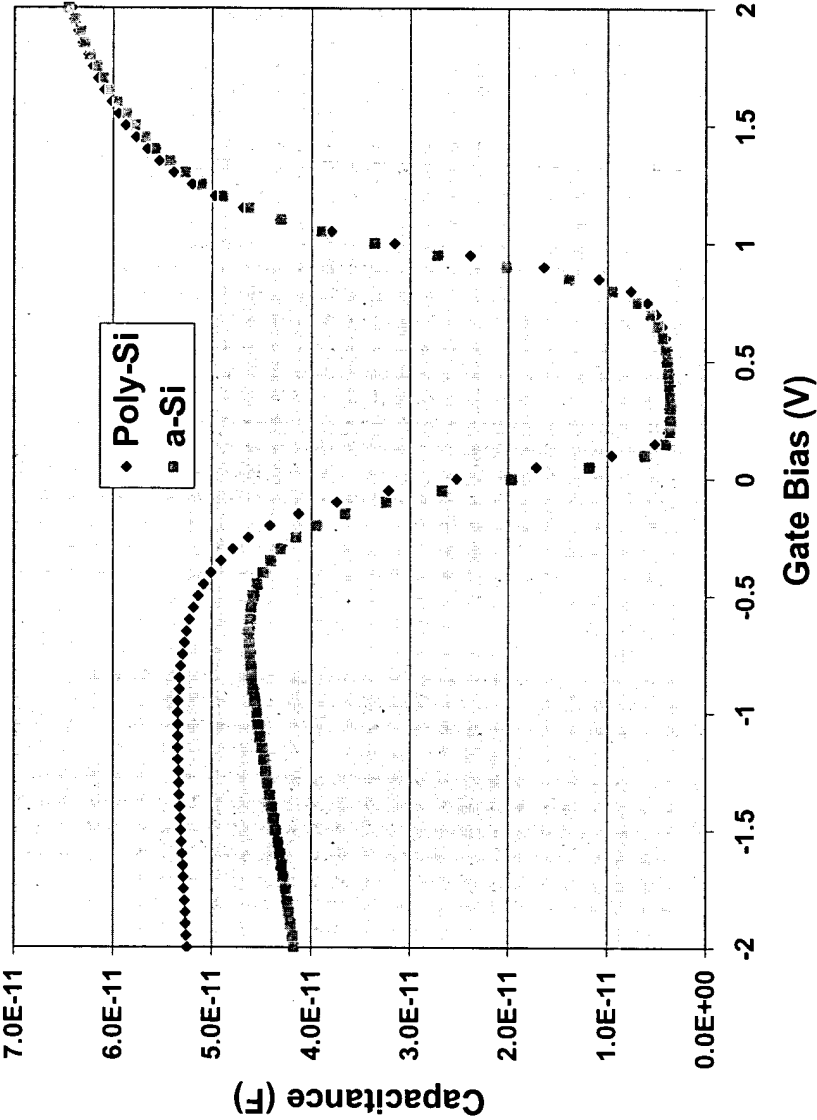


FIGURE 12

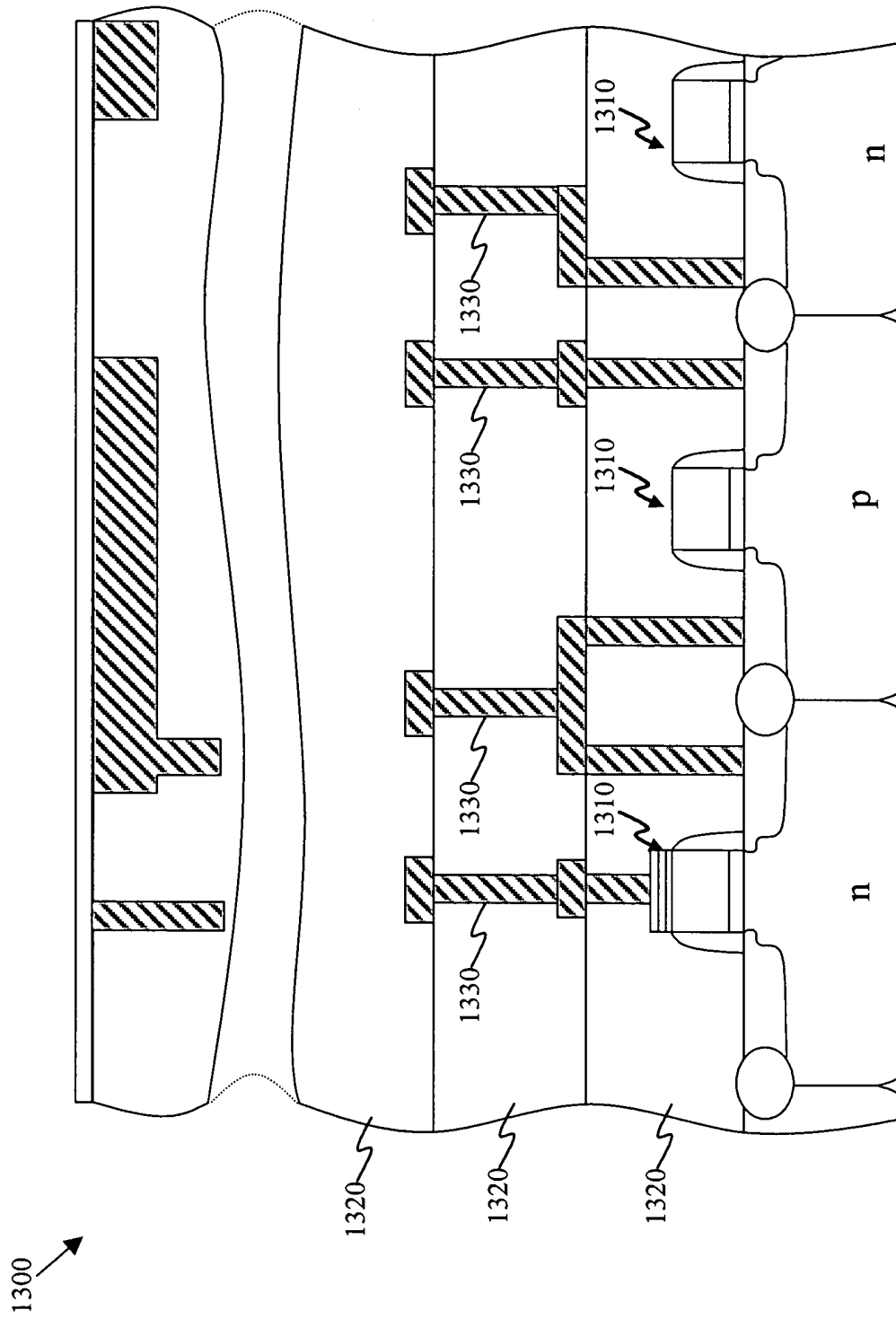


FIGURE 13